

IN THE CLAIMS

1. **(Currently Amended)** An electron beam exposure mask comprising:

a main mask having a plurality of first defined masks; and

one or more compensation masks including one or more non-defective second defined masks each having a pattern configuration which is intended to be formed ~~in~~ within a defective first defined mask among said plurality of first defined masks.

2. **(Original)** The electron beam exposure mask according to claim 1, wherein said main mask and at least one compensation mask are arranged on the same substrate.

3. **(Currently Amended)** The electron beam exposure mask according to claim 1, wherein said compensation mask includes one or more non-defective third defined masks each having a pattern configuration which is intended to be formed ~~in part~~ within one of said plurality of first defined ~~masks irrespective of the presence or absence of a defective among masks, regardless of whether there is a defect in~~ said plurality of first defined masks.

4. **(Original)** The electron beam exposure mask according to claim 3, wherein said compensation mask includes a plurality of identically patterned defined masks.

5. **(Original)** The electron beam exposure mask according to claim 3, wherein said second defined masks are arranged adjacent to said main mask.

6. **(Original)** The electron beam exposure mask according to claim 3, wherein said second defined masks are arranged in the periphery of said main mask.

7. **(Original)** The electron beam exposure mask according to claim 1, wherein the electron beam exposure mask constitutes a membrane mask or a stencil mask.

8.-12. **(Cancelled).**